

Analytical Methods for Materials

Lesson 4

Metallography

Suggested Reading

•Y. Leng, *Materials Characterization, 2nd Edition*, (2013), Wiley, Hoboken, NJ – Chapter 1.

Reference

•Goodhew, Humphreys and Beanland, Chapter 1

•Brandon and Kaplan, Chapter 3, pp. 123-177

•K. Geels, D.B. Fowler, W-U. Kopp, and M. Rückert, <u>Metallographic and Materialographic Specimen</u> <u>Preparation, Light Microscopy, Image Analysis and Hardness Testing</u>, (2007) ASTM International, West Conshohocken, PA.

•G.F. Vander Voort, Metallography Principles and Practice, (1999) ASM International, Materials Park, OH. 8

Metallography:

- A systematic method to examine microstructure of materials (mainly metallic materials).
- Can also be used to examine ceramics, polymers and semiconductors.

(1) Sectioning

Why sectioning?

- 1. Size limitation of specimen to be examined under optical microscope.
- 2. Locate area needs to be selected from a large sample.

Sample Preparation sectioning

• Abrasive Cutting is the most common sectioning method.



Sample Preparation sectioning

Electric Discharge Machining (EDM)

- Electrically conductive materials can be produced via EDM.
- Cutting is accomplished by an electric discharge between an electrode and the sample submerged in a dielectric fluid.

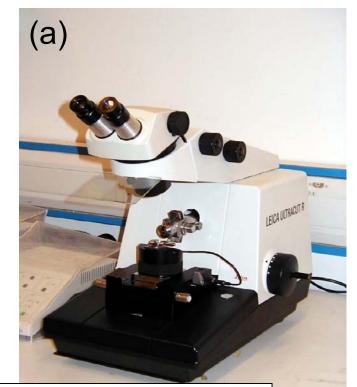


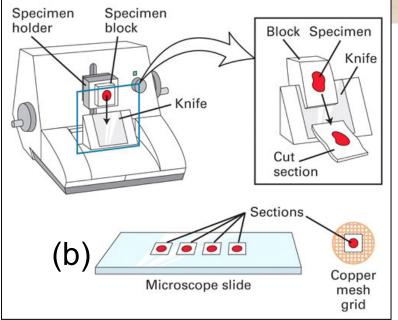
http://en.bhmachinery.com/login/images/upload/20092141553480249.jpg

Sample Preparation sectioning

Microtomy:

- Useful for preparing soft materials such as polymer samples.
- Steel, glass or diamond knives in a microtome can cut samples into very thin sections.



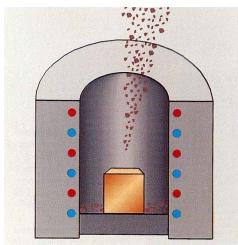


(2) Mounting

Required when (1) the sample is small or too oddly shaped to be handled. (2) The sample edge area needs to be examined

Thermal Mounting:

The sample is encased in thermosetting or thermoplastic polymers at high temperature and pressure



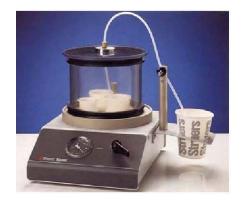


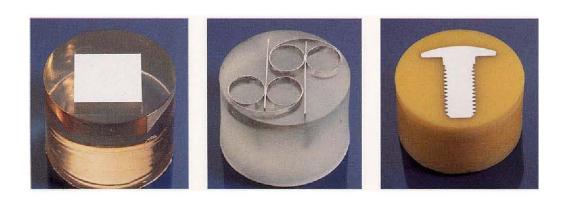
Adapted from MECH 4430 Lecture notes by Dr. Jingshen Wu and Dr. Yang Leng, Department of Mechanical Engineering, Hong Kong University of Science and Technology (http://www.me.ust.hk/~mejswu/).

Cold Mounting:

The sample is encased in epoxy type materials. Type of epoxy depends upon material being analyzed.







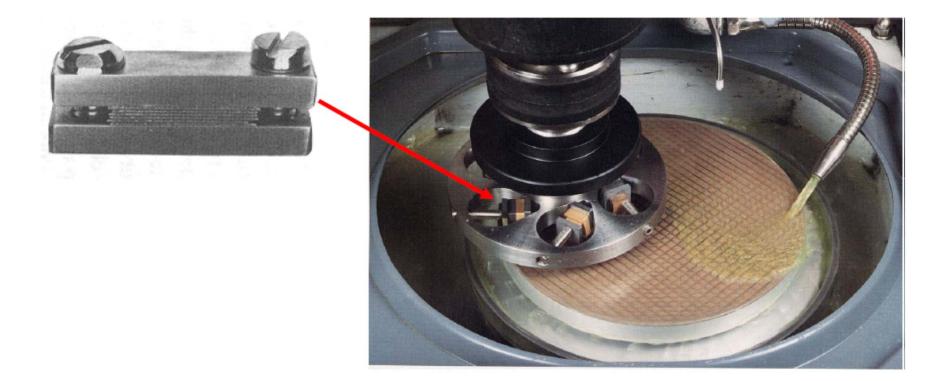
Hot Mounting Materials Features Material Name Application Specific property Resin 1 Electrically Acrylic Electropolishing conductive Thermoplastic Low shrinkage Resin 3 Transparent mounts Transparent Acrylic Porous material Low shrinkage Thermoplastic Resin 5 Hard Edge retention Good adhesion Epoxy Planeness Thermosetting Wear resistant For highest requirements No shrinkage Resin 6 Bakelite Serial mounting Medium shrinkage Thermosetting Pre-Mounts Bakelite Serial mounting of un-Easy to handle complicated shapes Medium shrinkage Thermosetting

Cold Mounting Materials

| Name | Features | | Material/filler | |
|-----------|--|---|---|--|
| | Application | Specific property | Curing time | Moulds |
| Citofix | Serial mounting Irregularly shaped specimens | Low viscosity Good adhesion Translucent Low shrinkage | Acrylic 7 - 10 min | Epoform Flexiform Seriform Monoform |
| Durofix | Serial mounting Edge retention Irregularly shaped specimens | Low viscosity Hard Wear resistant Low shrinkage | Acrylic Mineral fillers 15 min | Epoform Flexiform Seriform Monoform |
| Triofix-2 | Edge retention Planeness | Good adhesion Very hard Wear resistant Very low shrinkage | Polyester/ Acrylic/ Mineral filler 15 - 18 min | Epoform Flexiform Monoform |
| Epofix | Vacuum impregnation Porous samples Mineralogical samples | Low vapour- pressure Transparent Good adhesion Low viscosity No shrinkage | Epoxy 8 h | Epo <mark>f</mark> orm |
| Caldofix | Vacuum impregnation Porous samples Mineralogical samples | Low vapour- pressure Transparent Good adhesion Low viscosity Very low shrinkage | Epoxy 1 h at 80°C | Epoform |

Adhesive Mounting: The sample is glued to a piece of a large holder

<u>Clamp Mounting</u>: The sample is fixed in mechanical clamping devices



(3) Grinding

- 1. Removes the damage from the surface produced by sectioning.
- 2. Grinding also produces damage which must be minimized by subsequent grinding with finer abrasives.
- 3. At the end of grinding phase, the only grinding damage present must be from the last grinding step.
- 4. Such damage will be removed by polishing.

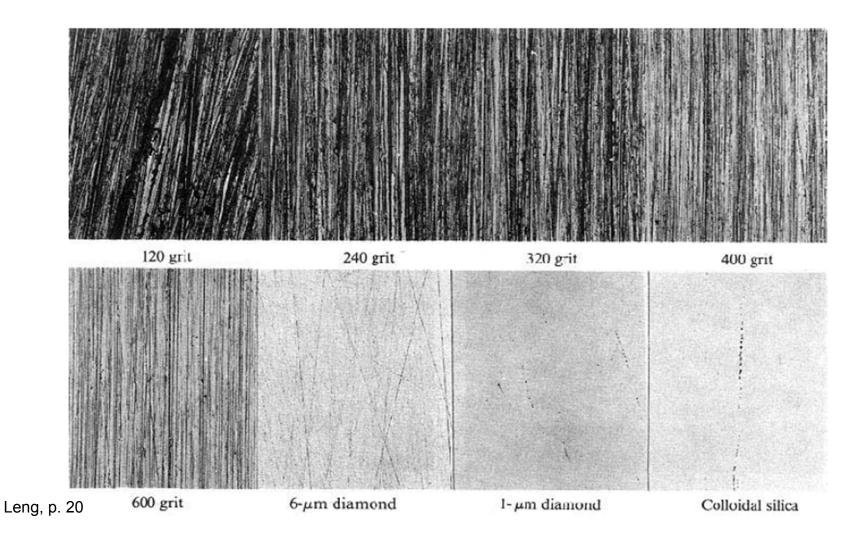
<u>Grinding Materials:</u> Abrasive paper (covered with silicon carbide grit). Commonly a series of abrasive papers are used from coarse to fine.

<u>Typical Grit Sequence:</u> 120-, 240-, 320-, 400-, 600-, 1200-, 2400-, etc.

- The initial grit size depends on the surface roughness and depth of damage from sectioning.
- Surfaces cut with abrasive cutoff saws generally start with 120- to 240- grit surface finishes.
- Surfaces cut by EDM or diamond saws generally start with 320- to 400- grit surface finishes.







Specimen surfaces after grinding and polishing.

(4) Polishing

After being ground to a 600-grit finish (or better), the sample is polished to produce a flat and scratch-free surface with high reflectivity.

<u>Coarse polishing</u>: abrasives in the range of 30 μ m to ~3 μ m using diamond grits of the appropriate size.

<u>Fine polishing</u>: abrasives in the range of $1\mu m$ or less using diamond grits of the appropriate size.

Final polishing: 0.25-0.05 µm diamond, silica, or alumina slurries.

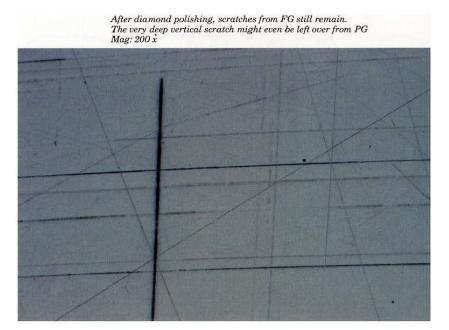
Automatic Polishing Machines



Figure 1.24 Polishing on a rotating wheel with a mechanical sample holder. From Leng, p. 21.

Artifact structure from improper grinding

Surface deformation from improper grinding should be avoided, otherwise the microstructure may be obscured.

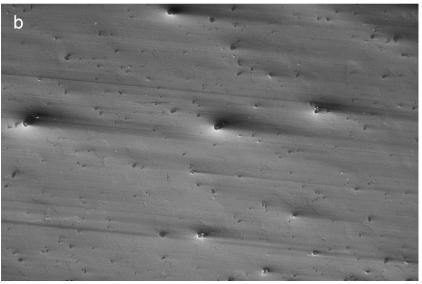


Artifacts from improper polishing

Polishing should produce a scratch-free surface.

Too much pressure can cause artifacts such as the comet tail artifacts shown below.

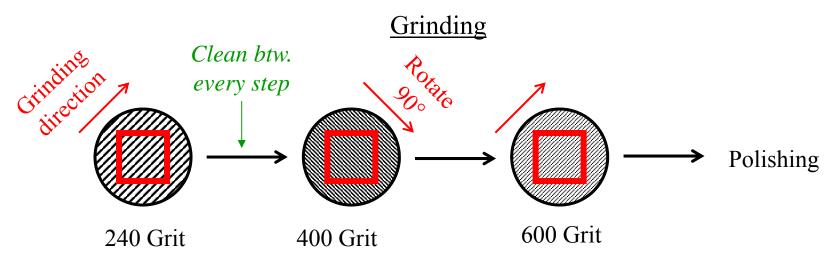




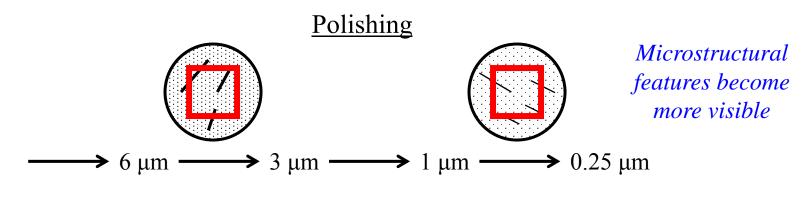
Bright-field image

DIC image

From page 22 in Leng



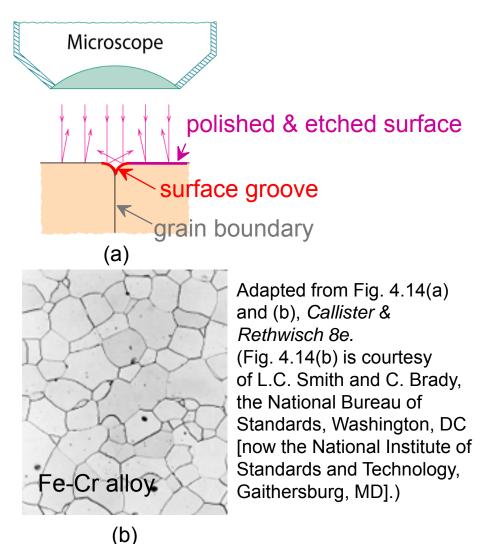
Check under LOM after each step



Optical Microscopy

(5) Etching

- Using chemicals to selectively dissolve the surface of a material in order to reveal microstructural details
- Grain boundaries are more susceptible to etching.
- May be revealed as dark lines.
- Due to change in crystal orientation across GB.



electrolytic polishing/etching

Etching is basically a controlled corrosion process. Results from electrolytic action between surface areas of different potential.

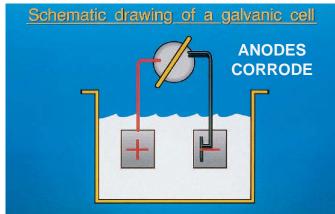
Electrolytic activity results from local physical or chemical heterogeneities which render some features anodic and others cathodic under the specific etching conditions.

Chemical Etchants produce contrast by

- Crystal faceting
- Selective phase dissolution.

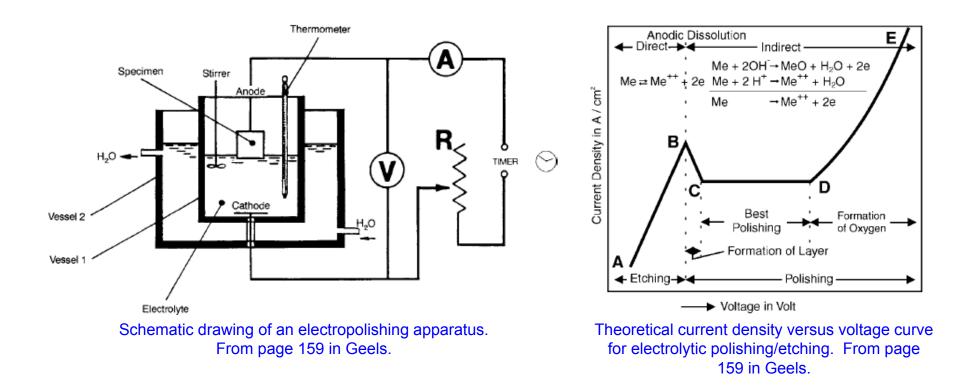
Common chemical etchants have three components:

- A corrosive agent (acids)
- A modifier (alcohol, glycerin...)
- An oxidizer (hydrogen peroxide, Fe³⁺, Cu²⁺...)



From page 156 in Geels

electrolytic polishing/etching



- Specific conditions are needed to ensure best polishing.
- Same procedures can be used to anodize materials.